

**PHOTOMASK, FLARE MEASURING MECHANISM, FLARE MEASURING METHOD, AND  
EXPOSING METHOD**

**Abstract of the Disclosure**

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Each of patterns on two types of photomasks including identical central pattern portions each having a line pattern formed on the center of a substrate, and peripheral pattern portions formed around the central pattern portions; and having distance between the central pattern portion and the peripheral pattern portion different from each other, is transferred on a wafer. Thereafter, each line width of the transferred patterns corresponding to the line pattern of each photomask is measured. The difference between each of line widths is obtained, wherefrom the flare rate is calculated.

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